

Customer No.: 31561  
Application No.: 10/709,036  
Docket No.: 12468-US-PA

### AMENDMENT

Please amend the application as indicated hereafter.

#### In the Claims :

1. (original) A laser annealing apparatus, adapted to perform a laser annealing process for annealing an amorphous silicon thin film, comprising:

a laser-generating module, adapted to provide a laser beam to recrystallize the amorphous silicon thin film to form a polysilicon thin film;

a resistance-measurement module, adapted to measure a sheet resistance of the polysilicon thin film for obtaining a sheet resistance value; and

a host circuit module, electrically coupled to and between the laser-generating module and the resistance-measurement module, the host circuit module, according to the sheet resistance value, outputting a feedback signal to the laser-generating module, for optimizing an energy density of the laser beam.

2. (original) The laser annealing apparatus of claim 1, further comprising a supporting module, wherein the supporting module is moveably located between the laser-generating module and the resistance-measurement module, adapted to support the amorphous silicon thin film, and electrically coupled to the host circuit module.

3. (original) The laser annealing apparatus of claim 1, wherein the laser-generating module comprises:

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a laser beam source; and  
a control circuit, electrically coupled to and between the laser beam source and the host circuit module.

4. (original) The laser annealing apparatus of claim 3, wherein the laser beam source comprises an excimer laser.

5. (original) The laser annealing apparatus of claim 1, wherein the resistance-measurement module comprises:

a measurement terminal; and  
an output circuit, electrically coupled to and between the measurement terminal and the host circuit module.

6. (original) The laser annealing apparatus of claim 5, wherein the measurement terminal comprises a probe set.

7. (original) The laser annealing apparatus of claim 1, wherein the host circuit module is installed in a database, and the host circuit module is adapted to compare the sheet resistance with a plurality of referential resistance values stored in the database for generating the feedback signal.

8.-11.(canceled)